IN THE CLAIMS

1. (Currently Amended) A tandem vacuum processing chamber, comprising:

a chamber body having bottom, outer sidewall and an interior sidewall, ~~defining~~ first and second processing regions defined in the chamber body and bound by the interior sidewall, the outer sidewall, and the bottom, the first and the second processing regions each comprising:

~~a bottom wall;~~

~~an interior sidewall positioned in communication with the bottom wall and configured to separate the first processing region from the second processing region, wherein each of the processing region has~~ a single substrate transfer port formed through ~~an~~ the outer sidewall of the chamber body;

a substrate support assembly centrally positioned in each of the first and second processing regions;

a first gas distribution assembly positioned above the first processing region; and

a second gas distribution assembly positioned above the second processing region.

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2. (Original) The processing chamber of claim 1, wherein the first and second gas distribution assemblies each comprise:

a gas distribution manifold in fluid communication with a gas supply; and

a showerhead positioned between the gas distribution manifold and the substrate support assembly.

3. (Original) The processing chamber of claim 2, wherein the showerhead is manufactured from a material that conducts radio frequency energy.

4. (Previously Presented) The processing chamber of claim 1, further comprising an annular pumping channel positioned in the interior sidewall of the first and second processing regions.